

Nikolai Salashchenko

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159 papers	1,237 citations	19 h-index	28 g-index
163 ext. papers	1,403 ext. citations	1 avg, IF	4.2 L-index

#	Paper	IF	Citations
159	Magnetic nanodot arrays produced by direct laser interference lithography. <i>Applied Physics Letters</i> , 2001 , 79, 2606-2608	3.4	67
158	Resonant diffraction of synchrotron radiation by a nuclear multilayer. <i>Physical Review Letters</i> , 1993 , 71, 2489-2492	7.4	55
157	Cr /sc multilayers for the soft-x-ray range. <i>Applied Optics</i> , 1998 , 37, 719-28	1.7	51
156	Roughness measurement and ion-beam polishing of super-smooth optical surfaces of fused quartz and optical ceramics. <i>Optics Express</i> , 2014 , 22, 20094-106	3.3	48
155	Next generation nanolithography based on Ru/Be and Rh/Sr multilayer optics. <i>AIP Advances</i> , 2013 , 3, 082130	1.5	44
154	Advanced materials for multilayer mirrors for extreme ultraviolet solar astronomy. <i>Applied Optics</i> , 2016 , 55, 2126-35	0.2	41
153	Ion-beam polishing of fused silica substrates for imaging soft x-ray and extreme ultraviolet optics. <i>Applied Optics</i> , 2016 , 55, 1249-56	0.2	39
152	High performance La/B4C multilayer mirrors with barrier layers for the next generation lithography. <i>Applied Physics Letters</i> , 2013 , 102, 011602	3.4	38
151	A source of a reference spherical wave based on a single mode optical fiber with a narrowed exit aperture. <i>Review of Scientific Instruments</i> , 2008 , 79, 033107	1.7	34
150	Extended model for the reconstruction of periodic multilayers from extreme ultraviolet and X-ray reflectivity data. <i>Journal of Applied Crystallography</i> , 2017 , 50, 1428-1440	3.8	31
149	Problems in the application of a null lens for precise measurements of aspheric mirrors. <i>Applied Optics</i> , 2016 , 55, 619-25	0.2	29
148	Multilayer X-ray mirrors based on La/B4C and La/B9C. <i>Technical Physics</i> , 2010 , 55, 1168-1174	0.5	26
147	Note: A stand on the basis of atomic force microscope to study substrates for imaging optics. <i>Review of Scientific Instruments</i> , 2015 , 86, 016102	1.7	25
146	Multilayer Zr/Si filters for EUV lithography and for radiation source metrology 2008 ,		25
145	Resolving capacity of the circular Zernike polynomials. <i>Optics Express</i> , 2015 , 23, 14677-94	3.3	22
144	Particulars of studying the roughness of substrates for multilayer X-ray optics using small-angle X-ray reflectometry, atomic-force, and interference microscopy. <i>Bulletin of the Russian Academy of Sciences: Physics</i> , 2011 , 75, 67-72	0.4	22
143	Current status and development prospects for multilayer X-ray optics at the Institute for Physics of Microstructures, Russian Academy of Sciences. <i>Journal of Surface Investigation</i> , 2017 , 11, 1-19	0.5	21

142	Thin film multilayer filters for solar EUV telescopes. <i>Applied Optics</i> , 2016 , 55, 4683-90	0.2	19
141	Short-period multilayer X-ray mirrors. <i>Journal of Synchrotron Radiation</i> , 2003 , 10, 358-60	2.4	19
140	Influence of barrier interlayers on the performance of Mo/Be multilayer mirrors for next-generation EUV lithography. <i>Optics Express</i> , 2018 , 26, 33718-33731	3.3	18
139	The evolution of roughness of supersmooth surfaces by ion-beam etching. <i>Bulletin of the Russian Academy of Sciences: Physics</i> , 2012 , 76, 163-167	0.4	17
138	Laboratory reflectometer for the investigation of optical elements in a wavelength range of 5–50 nm: description and testing results. <i>Quantum Electronics</i> , 2017 , 47, 385-392	1.8	16
137	Absolute photometry of pulsed intense fluxes of ultrasoft X-ray radiation. <i>Physica Scripta</i> , 1991 , 43, 356-367	3.67	16
136	Observation of extreme ultraviolet light emission from an expanding plasma jet with multiply charged argon or xenon ions. <i>Applied Physics Letters</i> , 2018 , 113, 153502	3.4	15
135	Application of point diffraction interferometry for middle spatial frequency roughness detection. <i>Optics Letters</i> , 2015 , 40, 159-62	3	14
134	Carbon K-edge polarimetry with Cr/Sc multilayers. <i>Journal of Physics: Conference Series</i> , 2013 , 425, 122013	1.3	14
133	A stand for a projection EUV nanolithographer-multiplier with a design resolution of 30 nm. <i>Bulletin of the Russian Academy of Sciences: Physics</i> , 2011 , 75, 49-52	0.4	14
132	Conversion efficiency of a laser-plasma source based on a Xe jet in the vicinity of a wavelength of 11 nm. <i>AIP Advances</i> , 2018 , 8, 105003	1.5	14
131	Study of oxidation processes in Mo/Be multilayers. <i>AIP Advances</i> , 2018 , 8, 075202	1.5	12
130	Testing and correction of optical elements with subnanometer precision. <i>Nanotechnologies in Russia</i> , 2008 , 3, 602-610	0.6	12
129	Fabrication and investigation of imaging normal-incidence multilayer mirrors with a narrow-band reflection in the range 4.5–5 nm. <i>Physica Scripta</i> , 1993 , 48, 516-520	2.6	12
128	Device for the precise shape correction of optical surfaces by ion-beam and reactive plasma etching. <i>Journal of Surface Investigation</i> , 2013 , 7, 913-915	0.5	11
127	Extreme-ultraviolet source based on the electron-cyclotron-resonance discharge. <i>JETP Letters</i> , 2008 , 88, 95-98	1.2	11
126	Reflective Schmidt-Cassegrain system for large-aperture telescopes. <i>Applied Optics</i> , 2016 , 55, 4430-5	0.2	11
125	A double-stream Xe:He jet plasma emission in the vicinity of 6.7 nm. <i>Applied Physics Letters</i> , 2018 , 112, 221101	3.4	11

124	Deposition of Mo/Si multilayers onto MEMS micromirrors and its utilization for extreme ultraviolet maskless lithography. <i>Journal of Vacuum Science and Technology B: Nanotechnology and Microelectronics</i> , 2017 , 35, 062002	1.3	10
123	Evolution of the roughness of amorphous quartz surfaces and Cr/Sc multilayer structures upon exposure to ion-beam etching. <i>Bulletin of the Russian Academy of Sciences: Physics</i> , 2011 , 75, 61-63	0.4	10
122	Componentry of reflection optics for application in the thesis X-ray astrophysics experiment. <i>Bulletin of the Russian Academy of Sciences: Physics</i> , 2010 , 74, 50-52	0.4	10
121	Physical limitations of measurement accuracy of the diffraction reference wave interferometers. <i>Bulletin of the Russian Academy of Sciences: Physics</i> , 2010 , 74, 53-56	0.4	10
120	Shortwave projection nanolithography. <i>Herald of the Russian Academy of Sciences</i> , 2008 , 78, 279-285	0.7	10
119	Influence of annealing on the structural and optical properties of thin multilayer EUV filters containing Zr, Mo, and silicides of these metals 2009 ,		9
118	Magnetic ordering in Fe-containing spinodally decomposing materials synthesized from laser plasma. <i>Physical Review B</i> , 1995 , 52, 10303-10314	3.3	9
117	Effect of structural defects of aperiodic multilayer mirrors on the properties of reflected (sub)femtosecond pulses. <i>Quantum Electronics</i> , 2017 , 47, 378-384	1.8	8
116	Preparation and roughness metrology of supersmooth optical surfaces. <i>Journal of Surface Investigation</i> , 2015 , 9, 761-764	0.5	8
115	Precision aspherization of the surface of optical elements by ion-beam etching. <i>Journal of Surface Investigation</i> , 2015 , 9, 765-770	0.5	8
114	Novel instrumentation for spectrally resolved soft x-ray plasma tomography: Development and pilot results on TEXTOR. <i>Review of Scientific Instruments</i> , 2001 , 72, 1411	1.7	8
113	Investigation of supersmooth optical surfaces and multilayer elements using soft X-ray radiation. <i>Technical Physics</i> , 2013 , 58, 1371-1379	0.5	7
112	Problem of roughness detection for supersmooth surfaces 2011 ,		7
111	Multilayer thin-film filters of extreme ultraviolet and soft X-ray spectral regions. <i>Bulletin of the Russian Academy of Sciences: Physics</i> , 2010 , 74, 46-49	0.4	7
110	Analysis of cross-correlation of interface roughness in multilayer structures with ultrashort periods. <i>Journal of Experimental and Theoretical Physics</i> , 2006 , 103, 346-353	1	7
109	Observation of laser-induced local modification of magnetic order in transition metal layers. <i>JETP Letters</i> , 2001 , 73, 192-196	1.2	7
108	The diffraction efficiency of echelle gratings increased by ion-beam polishing of groove surfaces. <i>Technical Physics Letters</i> , 2016 , 42, 844-847	0.7	7
107	Chemically amplified resists for high-resolution lithography. <i>Russian Microelectronics</i> , 2013 , 42, 165-175	0.5	6

106	Polished siall substrates for X-ray optics. <i>Journal of Surface Investigation</i> , 2013 , 7, 612-616	0.5	6
105	Application of cluster beams for the physics and technologies of microstructures. <i>Journal of Surface Investigation</i> , 2017 , 11, 496-500	0.5	6
104	Multilayer mirror systems to form hard X-ray beams. <i>Open Physics</i> , 2005 , 3,	1.3	6
103	Sub-micrometer resolution proximity X-ray microscope with digital image registration. <i>Review of Scientific Instruments</i> , 2015 , 86, 063701	1.7	5
102	Apparatus for the magnetron and ion-beam synthesis of multilayer structures. <i>Journal of Surface Investigation</i> , 2013 , 7, 637-639	0.5	5
101	An extreme ultraviolet radiation source based on plasma heated by millimeter range radiation. <i>Bulletin of the Russian Academy of Sciences: Physics</i> , 2011 , 75, 64-66	0.4	5
100	Two-mirror projection objective of a nanolithographer at λ 13.5 nm. <i>Bulletin of the Russian Academy of Sciences: Physics</i> , 2011 , 75, 57-60	0.4	5
99	Effect of roughness, deterministic and random errors in film thickness on the reflecting properties of aperiodic mirrors for the EUV range. <i>Quantum Electronics</i> , 2016 , 46, 406-413	1.8	5
98	Maskless X-Ray Lithography Based on Microoptical Electromechanical Systems and Microfocus X-Ray Tubes. <i>Journal of Surface Investigation</i> , 2018 , 12, 944-952	0.5	5
97	Microfocus X-Ray Tubes with a Silicon Autoemission Nanocathode as an X-Ray Source. <i>Bulletin of the Lebedev Physics Institute</i> , 2018 , 45, 1-5	0.5	5
96	Mo/Si Multilayer Mirrors with B ₄ C and Be Barrier Layers. <i>Journal of Surface Investigation</i> , 2019 , 13, 169-172	0.5	4
95	Set of Multilayer X-Ray Mirrors for a Double-Mirror Monochromator Operating in the Wavelength Range of 0.41–5.5 nm. <i>Journal of Surface Investigation</i> , 2019 , 13, 1-7	0.5	4
94	On the problems of the application of atomic-force microscopes for studying the surface roughness of elements for imaging optics. <i>Journal of Surface Investigation</i> , 2013 , 7, 797-801	0.5	4
93	Design of a soft X-ray and extreme UV reflectometer equipped with a high-resolution monochromator and high-brightness laser-plasma radiation source. <i>Journal of Surface Investigation</i> , 2015 , 9, 726-734	0.5	4
92	Applying reactive ionic-beam etching to correcting the shape of X-ray mirrors. <i>Bulletin of the Russian Academy of Sciences: Physics</i> , 2012 , 76, 168-170	0.4	4
91	Manufacturing and characterization of diffraction quality normal incidence optics for the XEUV range 2011 ,		4
90	Choosing optical materials for diagnostics of the solar atmosphere in the wavelength range of 680 nm. <i>Bulletin of the Russian Academy of Sciences: Physics</i> , 2011 , 75, 84-86	0.4	4
89	Interface Sensitive Investigation of ⁵⁷ Fe/Cr Superstructure by Means of Nuclear Resonance Standing Waves in Time Scale. <i>Hyperfine Interactions</i> , 2002 , 141/142, 119-123	0.8	4

88	Beryllium-Based Multilayer Mirrors for the Soft X-Ray and Extreme Ultraviolet Wavelength Ranges. <i>Journal of Surface Investigation</i> , 2020 , 14, 124-134	0.5	4
87	Current State of Development of a Microscope Operating at a Wavelength of 3.37 nm at the Institute of Physics of Microstructures of the Russian Academy of Sciences. <i>Journal of Surface Investigation</i> , 2018 , 12, 1253-1263	0.5	4
86	Stable Multilayer Reflective Coatings for $\lambda(\text{HeI}) = 58.4$ nm for the KORTES Solar Telescope. <i>Technical Physics Letters</i> , 2019 , 45, 85-88	0.7	3
85	X-ray scattering by the fused silica surface etched by low-energy Ar ions. <i>Journal of X-Ray Science and Technology</i> , 2019 , 27, 857-870	2.1	3
84	High performance multilayer La/B ₄ C mirrors with carbon barrier layers. <i>Bulletin of the Russian Academy of Sciences: Physics</i> , 2014 , 78, 61-63	0.4	3
83	Influence of the chemical structure of (co)polymer resists on their sensitivity to radiation. <i>Bulletin of the Russian Academy of Sciences: Physics</i> , 2012 , 76, 159-162	0.4	3
82	Possibility for the form correction of X-ray mirrors by reactive ion-beam etching. <i>Journal of Surface Investigation</i> , 2012 , 6, 487-489	0.5	3
81	Multilayer X-ray mirrors for the (4.48)-nm carbon-window spectral region. <i>Crystallography Reports</i> , 2013 , 58, 505-508	0.6	3
80	Deformation-free rim for the primary mirror of telescope having sub-second resolution 2017 ,		3
79	Surface shape measurement of mirrors in the form of rotation figures by using point diffraction interferometer. <i>Journal of Modern Optics</i> , 2017 , 64, 413-421	1.1	3
78	Effect of polymer matrix and photoacid generator on the lithographic properties of chemically amplified photoresist. <i>Russian Microelectronics</i> , 2014 , 43, 392-400	0.5	3
77	Reflective mask for projection lithography operating at a wavelength of 13.5 nm. <i>Journal of Surface Investigation</i> , 2012 , 6, 568-573	0.5	3
76	System for illumination of an EUV-nanolithograph mask. <i>Journal of Surface Investigation</i> , 2011 , 5, 517-519	0.5	3
75	A technological complex for manufacturing of precise imaging optics. <i>Bulletin of the Russian Academy of Sciences: Physics</i> , 2011 , 75, 53-56	0.4	3
74	New focusing multilayer structures for X-ray and VUV plasma spectroscopy. <i>Technical Physics</i> , 2010 , 55, 1018-1023	0.5	3
73	Fatigue in epitaxial lead zirconate titanate films. <i>Physics of the Solid State</i> , 1997 , 39, 609-610	0.8	3
72	X-ray and vacuum-ultraviolet plasma spectroscopy with the use of new focusing multilayer structures. <i>JETP Letters</i> , 2008 , 87, 27-29	1.2	3
71	New focusing multilayer structures for X-ray plasma spectroscopy. <i>Quantum Electronics</i> , 2008 , 38, 169-171	1.3	3

70	Development of Technological Principles for Creating a System of Microfocus X-Ray Tubes Based on Silicon Field Emission Nanocathodes. <i>Technical Physics</i> , 2019 , 64, 1742-1748	0.5	3
69	Electron Energy Conversion to EUV Radiation in the K α Line of Be in the Shooting Through Geometry. <i>Journal of Experimental and Theoretical Physics</i> , 2018 , 127, 985-993	1	3
68	Aperiodic Mirrors Based on Multilayer Beryllium Systems. <i>Journal of Surface Investigation</i> , 2019 , 13, 267-271	0.5	2
67	High-resolution laboratory reflectometer for the study of x-ray optical elements in the soft and extreme ultraviolet wavelength ranges. <i>Review of Scientific Instruments</i> , 2020 , 91, 063103	1.7	2
66	Observation of Laser-Induced Spark in the Density Jump in a Gas-Jet Target. <i>Technical Physics Letters</i> , 2019 , 45, 970-972	0.7	2
65	Using ion-beam etching to smooth fused silica surfaces. <i>Bulletin of the Russian Academy of Sciences: Physics</i> , 2014 , 78, 57-60	0.4	2
64	Thermal stability of a freestanding EUV filter under long-term vacuum annealing at 700–1000°C. <i>Journal of Surface Investigation</i> , 2012 , 6, 482-486	0.5	2
63	A laser plasma source of EUV radiation for projection nanolithography. <i>Bulletin of the Russian Academy of Sciences: Physics</i> , 2013 , 77, 6-9	0.4	2
62	Multilayer La/B4C mirrors in the spectral region near 6.7 nm. <i>Bulletin of the Russian Academy of Sciences: Physics</i> , 2013 , 77, 24-27	0.4	2
61	Freestanding multilayer films for application as phase retarders and spectral purity filters in the soft x-ray and EUV ranges 2011 ,		2
60	Mo-based EUV multilayer filters with enhanced thermal stability. <i>Bulletin of the Russian Academy of Sciences: Physics</i> , 2011 , 75, 73-75	0.4	2
59	Evolution of elemental distribution in free-standing structures of Zr/ZrSi ₂ with MoSi ₂ and ZrSi ₂ protective coatings under annealing. <i>Bulletin of the Russian Academy of Sciences: Physics</i> , 2011 , 75, 76-79	0.4	2
58	Details of how to mount high-precision optics. <i>Journal of Surface Investigation</i> , 2010 , 4, 359-365	0.5	2
57	A multilayer x-ray mirror in the form of an ellipsoid of revolution. <i>Bulletin of the Russian Academy of Sciences: Physics</i> , 2007 , 71, 64-67	0.4	2
56	Multilayer Cr/Sc Mirrors with Improved Reflection for the Water Transparency Window Range. <i>Technical Physics</i> , 2020 , 65, 1809-1813	0.5	2
55	Obtaining of Smooth High-Precision Surfaces by the Mechanical Lapping Method. <i>Technical Physics</i> , 2020 , 65, 1873-1879	0.5	2
54	Application of point diffraction interferometry for measuring angular displacement to a sensitivity of 0.01 arcsec. <i>Applied Optics</i> , 2015 , 54, 9315-9	0.2	2
53	Investigation of the thermo stability of aluminum thin-film filters with protective MoSi cap layers. <i>Applied Optics</i> , 2019 , 58, 21-28	1.7	2

52	Optical constants of sputtered beryllium thin films determined from photoabsorption measurements in the spectral range 20.4-250 eV. <i>Journal of Synchrotron Radiation</i> , 2020 , 27, 75-82	2.4	2
51	KORTES Mission for Solar Activity Monitoring Onboard International Space Station. <i>Frontiers in Astronomy and Space Sciences</i> , 2021 , 8,	3.8	2
50	Problems and prospects of maskless (B)EUV lithography 2016 ,		2
49	X-ray optical system for imaging laser plumes with a spatial resolution of up to 70 nm. <i>Quantum Electronics</i> , 2016 , 46, 347-352	1.8	2
48	Influence of Thermal Annealing on the Properties of Multilayer Mo/Be Mirrors. <i>Technical Physics</i> , 2019 , 64, 1692-1697	0.5	2
47	Influence of Beryllium Barrier Layers on the Properties of Mo/Si Multilayer Mirrors. <i>Technical Physics</i> , 2019 , 64, 1688-1691	0.5	2
46	Diffraction-limited short-wavelength optics: Analysis, fabrication, and application. <i>Journal of Surface Investigation</i> , 2012 , 6, 464-472	0.5	1
45	Nanostructure formation on an EUV lithographer stand: First results. <i>Bulletin of the Russian Academy of Sciences: Physics</i> , 2013 , 77, 1-5	0.4	1
44	The effect of bombardment with neutralized neon ions on the roughness of a fused silica and beryllium surface. <i>Journal of Surface Investigation</i> , 2017 , 11, 485-489	0.5	1
43	Measurement of the profile and curvature of cylindrical multilayer mirrors irradiated by a divergent X-ray beam. <i>Journal of Surface Investigation</i> , 2011 , 5, 526-528	0.5	1
42	SIMS study of annealing effect on element distribution in free-standing Al/Si and Zr/ZrSi ₂ multilayer films. <i>Journal of Surface Investigation</i> , 2010 , 4, 405-410	0.5	1
41	On creating multilayer X-ray focusing mirrors. <i>Bulletin of the Russian Academy of Sciences: Physics</i> , 2010 , 74, 38-40	0.4	1
40	Resonance enhancement of diffuse scattering of x-rays in a waveguide heterostructure. <i>JETP Letters</i> , 1997 , 66, 236-240	1.2	1
39	X-ray intensity distribution in the image plane of elliptic multilayer mirrors. <i>Journal of Surface Investigation</i> , 2007 , 1, 235-239	0.5	1
38	Multilayer x-ray mirrors based on W/B 4 C with ultrashort ($d = 0.7\text{--}1.5$ nm) periods. <i>Journal of Surface Investigation</i> , 2007 , 1, 7-12	0.5	1
37	Effect of pinhole roughness on light diffraction. <i>Journal of Surface Investigation</i> , 2008 , 2, 511-513	0.5	1
36	Absolute radiometry technique for VUV and SXR radiation fluxes. <i>Zeitschrift für Physik D-Atoms Molecules and Clusters</i> , 1991 , 21, S161-S162		1
35	Broadband Mirrors for Spectroheliographs at the KORTES Sun Study Facility. <i>Technical Physics</i> , 2020 , 65, 1792-1799	0.5	1

34	Application of Novel Multilayer Normal-Incidence Mirrors for EUV Solar Spectroscopy. <i>Technical Physics</i> , 2020 , 65, 1736-1739	0.5	1
33	The Smoothing Effect of Si Layers in Multilayer Be/Al Mirrors for the 17- to 31-nm Range. <i>Technical Physics</i> , 2020 , 65, 1786-1791	0.5	1
32	Mirrors with a Subnanometer Surface Shape Accuracy 2013 , 595-616		1
31	Reflecting properties of narrowband Si/Al/Sc multilayer mirrors at 58.4 nm. <i>Optics Letters</i> , 2020 , 45, 4666-4669	3	1
30	Prospects for the Use of X-Ray Tubes with a Field-Emission Cathode and a Through-Type Anode in the Range of Soft X-Ray Radiation. <i>Technical Physics</i> , 2020 , 65, 1726-1735	0.5	1
29	Measurement Error of Interferometers with Diffraction Reference Wave. <i>Technical Physics</i> , 2019 , 64, 1698-1703	0.5	1
28	Multilayer Ag/Y Mirrors for the Spectral Range of 911 nm. <i>Technical Physics</i> , 2019 , 64, 1684-1687	0.5	1
27	Beryllium as a Material for Thermally Stable X-Ray Mirrors. <i>Technical Physics</i> , 2019 , 64, 1596-1601	0.5	1
26	Fabrication and Study of a Concave Crystal Mirror for the KORTES Project. <i>Technical Physics</i> , 2019 , 64, 1680-1683	0.5	1
25	Modular Device for the Formation and Study of Cluster Beams of Inert and Molecular Gases. <i>Journal of Surface Investigation</i> , 2019 , 13, 862-869	0.5	1
24	Optimization of Composition, Synthesis, and Study of Broadband Multilayer Mirrors for the EUV Spectral Range. <i>Technical Physics</i> , 2019 , 64, 1673-1679	0.5	1
23	Emission Spectra of Light Inert Gases Ne and Ar in the 320 nm Range under Pulsed Laser Excitation Using Various Gas Jets as Targets. <i>Optics and Spectroscopy (English Translation of Optika i Spektroskopiya)</i> , 2021 , 129, 185-190	0.7	1
22	Optical, Mechanical, and Thermal Properties of Free-Standing MoSi ₂ N _x and ZrSi ₂ N _y Nanocomposite Films. <i>Technical Physics</i> , 2019 , 64, 1590-1595	0.5	0
21	The Microstructure of Transition Boundaries in Multilayer Mo/Be Systems. <i>Technical Physics</i> , 2020 , 65, 1800-1808	0.5	0
20	Ion-Beam Methods for High-Precision Processing of Optical Surfaces. <i>Technical Physics</i> , 2020 , 65, 1837-1845	0.5	0
19	Influence of ion-beam etching by Ar ions with an energy of 200-1000 eV on the roughness and sputtering yield of a single-crystal silicon surface.. <i>Applied Optics</i> , 2022 , 61, 2825-2833	1.7	0
18	Microstructure and Density of Mo Films in Multilayer Mo/Si Mirrors. <i>Journal of Surface Investigation</i> , 2019 , 13, 8-13	0.5	
17	Multilayer X-Ray Image-Forming Optics. <i>Bulletin of the Russian Academy of Sciences: Physics</i> , 2019 , 83, 105-111	0.4	

- 16 A Two-coordinate digital detector for microscopy in the soft X-ray region. *Bulletin of the Russian Academy of Sciences: Physics*, **2014**, 78, 64-67 0.4
- 15 Comparative heat load testing of freestanding multilayer Mo/ZrSi₂ and Mo/NbSi₂. *Bulletin of the Russian Academy of Sciences: Physics*, **2013**, 77, 83-85 0.4
- 14 Design of the aspheric Schwarzschild lens for a nanolithographer with the operating wavelength $\lambda = 13.5$ nm. *Journal of Surface Investigation*, **2011**, 5, 512-516 0.5
- 13 Project for manufacturing a Russian EUV nanolithographer for the fabrication of chips according to technological standards of 22 nm. *Bulletin of the Russian Academy of Sciences: Physics*, **2011**, 75, 44-48 0.4
- 12 Activity in manufacturing and characterization of X-ray optical elements and ultrahigh-resolution systems at IPM RAS. *Bulletin of the Russian Academy of Sciences: Physics*, **2009**, 73, 62-65 0.4
- 11 Normal-incidence multilayer mirrors for the 120-450 nm wavelength region. *Journal of X-Ray Science and Technology*, **1990**, 2, 241-8 2.1
- 10 Multilayer Dispersion Elements For X-Ray Emission At $\lambda = 17 - 100$ nm. **1985**, 0473, 298
- 9 The possibility of using a laser to obtain ultrathin continuous single-crystal films. *Radiophysics and Quantum Electronics*, **1975**, 18, 674-675 0.7
- 8 10.1007/s11448-008-1007-7 **2010**, 87, 27
- 7 Modification and Polishing of the Holographic Diffraction Grating Grooves by a Neutralized Ar Ion Beam. *Technical Physics*, **2020**, 65, 1780-1785 0.5
- 6 Projection Objective For an EUV-Lithographic Workbench. *Journal of Surface Investigation*, **2020**, 14, 562-573 0.5
- 5 Extending the Measurement Capabilities of a Model 130 Profilometer. *Journal of Surface Investigation*, **2019**, 13, 889-893 0.5
- 4 Emission Properties of Laser Plasma Excited on Molecular-Cluster Carbon Dioxide Jets. *Technical Physics*, **2019**, 64, 1566-1572 0.5
- 3 Emission Spectra of Heavy Inert Gases Kr and Xe in the Range from 3 to 20 nm Obtained under Pulsed Laser Excitation Using Various Gas Jets as Targets. *Optics and Spectroscopy (English Translation of Optika i Spektroskopiya)*, **2021**, 129, 363-368 0.7
- 2 Emission Spectra of Molecular Gases N₂ and CO₂ in the Range of 300 nm upon Pulsed Laser Excitation of Various Gas-Jet Targets. *Optics and Spectroscopy (English Translation of Optika i Spektroskopiya)*, **2021**, 129, 789-793 0.7
- 1 Y-Based Multilayer Mirrors for the Spectral Range of 8-12 nm. *Bulletin of the Lebedev Physics Institute*, **2021**, 48, 406-410 0.5